

DEC 29 2003

TRANSMITTAL OF FORMAL DRAWINGS

Docket No.

SLA0693

Re Application Of: David R. Evans, Sheng Teng Hsu, Bruce D. Ulrich, Douglas J. Tweet and Lisa H. Stecker

Serial No.	Filing Date	Batch No.	Examiner	Art Unit
10/606,105	06/25/2003		Lynne Ann Gurley	2812

Invention: Self-Aligned Shallow Trench Isolation Process Having Improved Polysilicon Gate Thickness Control

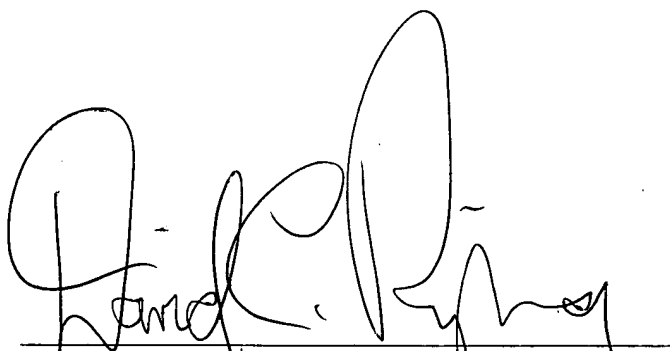
Address to:

Assistant Commissioner for Patents
Washington, D.C. 20231

Transmitted herewith are:

6 sheets of formal drawing(s) for this application.

Each sheet of drawing indicates the identifying indicia suggested in 37 CFR Section 1.84(c) on the reverse side of the drawing.



Signature

David C. Ripma, Patent Counsel
Registration No. 27,672
Sharp Laboratories of America, Inc.
5750 NW Pacific Rim Boulevard
Camas, WA 98607
Phone: 360-834-8754
Facsimile: 360-817-8505

Dated: December 23, 2003

I certify that this document and attached formal drawings are being deposited on December 23 2003 with the U.S. Postal Service as first class mail under 37 C.F.R. 1.8 and addressed to the Assistant Commissioner for Patents, Washington, D.C. 20231.

Signature of Person Mailing Correspondence

David C. Ripma, Reg. #27,672

Typed or Printed Name of Person Mailing Correspondence